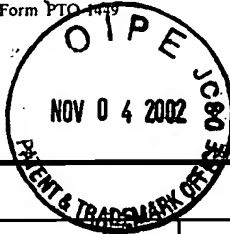


Form PTO 449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. MI22-1898		SERIAL NO. 10/050,348	
<div style="text-align: center;">  </div> <div style="text-align: center;"> LIST OF ART CITED BY APPLICANT (Use several sheets if necessary) </div>					APPLICANT Gurtej S. Sandhu et al.			
					FILING DATE January 15, 2002		GROUP 2813	
U.S. PATENT DOCUMENTS								
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate		
	AA	5,032,545	07/91	Doan et al.				
	AB	5,436,481	07/95	Egawa et al.				
	AC	5,378,645	01/95	Inoue et al.				
	AD	5,258,333	11/93	Shappir et al.				
	AE	5,518,946	05/96	Kuroda				
	AF	5,445,999	08/95	Thakur et al.				
	AG	5,382,533	01/95	Ahmad et al.				
	AH	5,663,077	09/97	Adachi et al.				
	AI	5,026,574	06/91	Economu et al.				
	AJ	5,026,574~	06/91	Economu et al.				
	AK	5,612,558	11/95	Harshfield				
	AL	5,719,083	06/95	Komatsu				
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AM	WO 96/39713	12/96	PCT				
	AN							
	AO							
	AP							
	AQ							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AR		Wolf, S., "Silicon Processing for the VLSI Era", Lattice Press 1990, Vol. 2, pp. 212-213.					
	AS		Wolf, S., "Silicon Processing for the VLSI Era", Lattice Press 1990, Vol. 2, pp. 188-189, 194-195, 609-614.					
	AT		Ko, L. et al., "The Effect of Nitrogen Incorporation into the Gate Oxide By Using Shallow Implantation of Nitrogen and Drive-In Process", IEEE 1996, pp. 32-35.					
EXAMINER				DATE CONSIDERED				
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>								

Form PTO-449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. MI22-1898		SERIAL NO. 09/633,556	
<div style="position: relative; height: 100px;"> <div style="position: absolute; top: 0; left: 0; width: 100%; height: 100%; border: 2px solid black; border-radius: 50%; text-align: center; font-size: 24px; line-height: 1;"> U.S. PATENT & TRADEMARK OFFICE NOV 04 2002 </div> </div>					LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)			
					APPLICANT Gurtej S. Sandhu et al.			
					FILING DATE August 7, 2000		GROUP 2813	
U.S. PATENT DOCUMENTS								
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate		
	AA	5,760,475	06/98	Cronin				
	AB	5,834,372	11/98	Lee				
	AC	5,619,057	04/96	Komatsu				
	AD	5,633,036	05/97	Seebauer et al.				
	AE	6,054,396	04/00	Doan				
	AF	6,174,821	01/01	Doan				
	AG	5,939,750	08/99	Early				
	AH	5,254,489	10/93	Nakata				
	AI	5,464,792	11/95	Tseng et al.				
	AJ	5,620,908	04/97	Inoh et al.				
	AK	5,716,864	02/98	Abe				
	AL	5,972,783	10/99	Arai et al.				
FOREIGN PATENT DOCUMENTS								
	Document Number	Date	Country	Class	Subclass	Translation		
						Yes	No	
	AM							
	AN							
	AO							
	AP							
	AQ							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AR	Doyle, B. et al., "Simultaneous Growth of Different Thickness Gate Oxides in Silicon CMOS Processing", IEEE Vol. 16 (7), July 1995, pp. 301-302.						
	AS	Kuroi, T. et al., "The Effects of Nitrogen Implantation Into P+Poly-Silicon Gate on Gate Oxide Properties", 1994 Sympos. on VLSI Technology Digest of Technical Papers, IEEE 1994, pp. 107-108.						
	AT	Liu, C.T. et al., "Multiple Gate Oxide Thickness for 2GHz System-on-a-Chip Technologies", IEEE 1998, pp. 589-592.						
EXAMINER				DATE CONSIDERED				
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								

EV182658911

Form PTO-159 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-1898		SERIAL NO. 09/633,556	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Gurtej S. Sandhu et al.	
FILING DATE August 7, 2000				GROUP 2813	

NOV 04 2002
 U.S. PATENT & TRADEMARK OFFICE

U.S. PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
AA	6,091,109	07/00	Hasegawa				
AB	6,080,682	06/00	Ibok				
AC	5,685,949	11/97	Yashima				
AD	6,268,296 B1	07/01	Misium et al.				
AE	6,232,244 B1	05/01	Ibok				
AF	6,331,492	12-2001	Misium et al.				
AG	6,080,629	06-2000	Gardner et al.				
AH	5,970,345	10-1999	Hattangady et al.				
AI	5,885,877	03-1999	Gardner et al.				
AJ	6,323,114 B1	11-2001	Hattangady et al.				
AK	6,184,110 B1	02-2001	Ono et al.				
AL							

FOREIGN PATENT DOCUMENTS							
	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
AM							
AN							
AO							
AP							
AQ							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
AR			
AS			
AT			

EXAMINER <i>Walter Schultz</i>	DATE CONSIDERED 3/1/03
-----------------------------------	---------------------------

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.